

ABSTRACT OF THE DISCLOSURE

This invention relates to an apparatus for splash-back proofing, being used for treating a panel or substrate in photolithographic process. The present invention prevents a liquid (such as developer or photoresist solution) dripping on the surface of the substrate or panel from splashing back to the substrate or panel after scattering to the periphery of the substrate or panel by spin-coating. The splashing-back liquid will bring about defects in the patterning or photolithographic process, and result in deterioration of products. The apparatus for splash-back proofing includes a rotating device, at least a liquid spray unit, a guard means surrounding part of the rotating device and a roughening unit. Also, a method for splash-back proofing is disclosed.